

IN THE CLAIMS:

Kindly cancel claims 17 and 22 without prejudice or disclaimer.

Please amend claims 12, 13, 18, 35, 45 and 55 as follows. A marked up version showing the changes made thereto is enclosed.

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B1 --12. (Amended) A processing apparatus having a processing chamber for processing a substrate or a film therein and an exhaust means for exhausting a gas from the processing chamber, comprising a trap means provided between the processing chamber and the exhaust means, for causing a chemical reaction in a non-reacted gas and/or a by-product during processing, said trap means provided in an exhaust gas flow path in an exhaust pipe provided between the processing chamber and the exhaust means, and a filament provided inside the trap means and comprised of a metal or an alloy comprising as a main component at least one of tungsten, molybdenum and rhenium.

13. (Amended) A processing apparatus having a processing space for processing a substrate or a film therein and an exhaust means for exhausting a gas from the processing space, comprising means provided between the processing space and the exhaust means, for causing a chemical reaction in a non-reacted gas and/or a by-product during processing of the substrate or the film, wherein the means comprises a heat generating chamber comprising phosphorous (P) atoms, said means for causing a chemical reaction provided in an exhaust gas flow path in an exhaust pipe provided between the processing chamber and the exhaust means.

18. (Amended) A processing apparatus having a processing space for processing a substrate or a film therein and an exhaust means for exhausting a gas from the processing space, comprising between the processing space and the exhaust means, means for causing a chemical reaction in a non-reacted gas and/or a by-product during processing of the substrate or the film, wherein the means comprises a heat generating member comprising silicon (Si) atoms, and wherein the means for causing the chemical reaction is provided in an exhaust gas flow path in an exhaust pipe provided between the processing space and the exhaust means.

35. (Twice Amended) A processing apparatus having a processing chamber and an exhaust means for exhausting a gas from the processing chamber, comprising, in an exhaust path connecting the processing chamber and the exhaust means, a region with a different mean velocity of the gas from that of the processing chamber, and a chemical reaction causing means provided in the region, for causing a chemical reaction in a non-reacted gas and/or a by product exhaust from the processing chamber, wherein the mean velocity of the gas of the region having the chemical reaction causing means is larger than the mean velocity of the processing chamber, wherein the chemical reaction causing means comprises a high-melting metal filament and wherein the chemical reaction causing means is provided in an exhaust gas flow path in an exhaust pipe provided between the processing space and the exhaust means.

B4

45. (Twice Amended) A processing apparatus having a processing space and an exhaust means for exhausting a gas from the processing space, comprising a chemical reaction causing means provided in an exhaust path connecting the processing space and the exhaust means, for causing a chemical reaction in a non-reacted gas and/or a by-product during the processing, and a cooling means disposed in the exhaust path in the vicinity of the chemical reaction causing means and provided on the side of the exhaust means of the chemical reaction causing means, said cooling means having an O-ring vacuum seal and being capable of controlling the temperature of the vacuum seal to prevent damage thereto.

B5

55. (Twice Amended) A processing apparatus having a processing space and an exhaust means for exhausting a gas from the processing space, comprising a chemical reaction causing means provided in an exhaust path between the processing space in a chamber and the exhaust means, for causing a chemical reaction in a non-reacted gas and/or a by-product during the processing, and a cooling means provided in at least a part of the exhaust path between the processing space and the exhaust means, said cooling means having an O-ring vacuum seal and being capable of controlling the temperature of the vacuum seal to prevent damage thereto.--

REMARKS

The claims are 12-16, 18-21, 23-27, 35, 38 and 45-55 with claims 12, 13, 18, 23, 35, 45 and 55 being independent. The subject matter of claim 17 has been added to